

SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING SYSTEM

Abstract

A substrate processing apparatus configured to process a substrate, the substrate processing apparatus including: a processing chamber; and a support member disposed in the processing chamber and having a tray supporting surface for supporting a tray on an upper surface of the support member, in which the tray is formed with a recess accommodating the substrate on an upper surface of the tray via a first heat transfer material, and the tray supporting surface is configured in such a manner that a second heat transfer material is interposed between the tray supporting surface and a lower surface side of the tray.

Fig. 4